

NILindustrialday 2023

April 17 and 18, Vienna



Day 1 – April 17

CEST

09:00	11:00	Setting up of exhibition
11:00	12:30	Arrival of participants/exhibition



	Affiliation	Speaker	Title
12:30	bmk, MRT, Profactor		Welcome

Session 1 – Session chair: Michael Hornung (GenISys)

12:40	Applied Materials	Rami Hourani	NIL Roadmap to make the optimal Waveguide
13:00	SÜSS MicroTec	Vijay Ramya Kolli	SUSS Imprint Solutions for High Quality Nano-optical Elements in AR/VR
13:20	Dispelix	Mikhail Omelyanovich	NIL approach for Augmented Reality industry
13:40	High RI Optics	Keiko Munechika	Filler-Free NIL Compatible Ultra-High Refractive Index Resins for Patterning Diffractive Optical Elements
14:00	micro resist technology	Arne Schleunitz	Industrial NIL materials: expectations and solutions

14:20 Coffee break / exhibition

Session 2 – Session chair: Pavel Kulha (Profactor)

15:00	Joanneum	Dieter Nees	 New Bio-Based Photo-Initiators for UV-Nano-Imprint Resins
15:20	imec	Eleonora Storace	Optimisation of nano-patterning for large-area high-density layouts
15:40	Inkron	Mikko Poutanen	Advances in spin coatable, and inkjettable high refractive index materials for nanoimprint processes
16:00	Profactor	Michael Haslinger	 Nanoimprinting of micro and nano-structures as for Life Science applications

16:20 Coffee break / exhibition

Session 3 – Chaired by MRT

17:00	EVG	Andrea Kneidinger	Nanoimprint Lithography: Ideal Manufacturing Technology for Advanced Photonic Devices
17:20	NILT	Theodor Nielsen	Meta Optical Elements Product by Nanoimprint Lithography
17:40	WaveOptics	Yury Stebunov	Production and Dimensional Metrology of AR Waveguides
18:00	Illumina	Tim Merkel	 NIL in Next Generation Sequencing

18:20 Social event, dinner



Federal Ministry
Republic of Austria
Climate Action, Environment,
Energy, Mobility,
Innovation and Technology



MEETING
DESTINATION
VIENNA
NOW • TOGETHER



NILindustrialday 2023

April 17 and 18, Vienna





Day 2 – April 18

CEST


08:00 08:50 Exhibition, arrival of participants

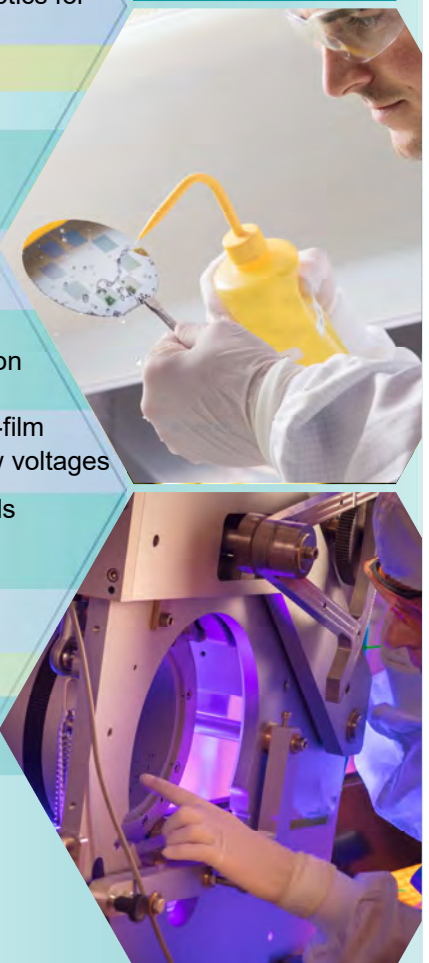
Affiliation	Speaker	Title
08:50 MRT & Profactor		Welcome

Session 4 – Session chair: Stefan Schrittwieser (AIT)

09:00	Kioxia (online)	Tetsuro Nakasugi	 Nanoimprint lithography: enabling future semiconductor manufacturing to be energy efficient
09:20	Wearoptimo (online)	Vignesh Suresh	 Manufacturing Microwearables for Continuous Health Monitoring
09:40	Silicon Austria Labs	Mustapha Chouiki	Nanofabrication for MEMS technology
10:00	Morphotonics	Sander Kommeren	Large-Area Nanoimprint: Challenges and Opportunities
10:20	SÜSS MicroOptics	Patrick Heissler	Enabling the volume: Imprinted micro-optics for automotive applications
10:40			Coffee break / exhibition

Session 5 – Session chair: James Watkins (Univ. Mass. Amherst)

11:20	SCIL	Marc Verschuuren	Nanometer-accurate nano-phonic optical structures in inorganic materials
11:40	FhG IoF	Robert Leitel	Sub-micron overlay accuracy Selective molding of microoptics
12:00	scia Systems	Philipp Böttger	Manufacturing of slanted surface relief gratings: Flexibility in trench design by ion beam trimming
12:20	SINTEF	Christopher Dirdal	MEMS-tunable metasurfaces using thin-film PZT, offering large displacements at low voltages
12:40	Stensborg	Oskar Darselius Berg	 Energy efficient coloration of solar panels
13:00	MRT & Profactor		Final announcements
13:10			Lunch
14:30			End of exhibition and NILindustrialday 2023



STENSBORG



Federal Ministry
Republic of Austria
Climate Action, Environment,
Energy, Mobility,
Innovation and Technology



MEETING
DESTINATION
VIENNA
NOW • TOGETHER